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**ZEON places a new production ZEP530A with the high resolution on the market for next-generation electronics devices.**

Zeon Corporation

**ZEON introduces ZEP530A for high resolution electron beam lithography for next-generation electronics devices.**

ZEP520A of ZEP series has been commercially available for over 20 years. ZEP is designed as a main chain scission-type positive-tone photoresist.

ZEON is proud to announce the commercialization of the next generation of the ZEP series, ZEP530A.

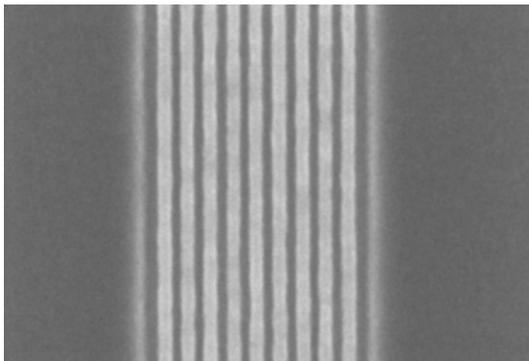
ZEP530A offers excellent dry etch resistance, wide litho process margins, and ultra-high resolution.

ZEP530A can easily resolve 17 nm half pitch line and space pattern.

Combining ZEP530A with the new developer, ZED-N60, an even higher resolution can be achieved.

ZEP530A is an excellent fit for manufacturing of next-generation electronics devices, including 5G wireless technology.

ZEP530A is the next benchmark for positive photoresists in electron beam lithography while ZEON continues the development roadmap for photoresists.



Film Thickness: 40nm

Electron Beam Lithography Exposure:

ELS-F150 (ELIONIX INC.)

\*Top-view of Scanning Electron Microscope

\*L/S : Line and Space Pattern